

以散條增進焦深與改善禁止間距之模擬

及全條減光散條之製備

The simulations of increasing DOF and improving Forbidden

Pitch by Scattering Bar (SB),

and fabrication of Whole Bar Attenuation (WBA)

碩士生：胡繼仁

Student: Hu Ji-ren

指導教授：龍文安博士

Advisor: Dr. Loong Wen-an

國立交通大學

應用化學研究所

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